

PATENT ABSTRACTS OF JAPAN

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(71)Applicant : SHARP CORP

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(72)Inventor : DOI MINORU

(54) SEMICONDUCTOR CLEANING EQUIPMENT

(57)Abstract:

PROBLEM TO BE SOLVED: To provide cleaning equipment wherein the increase of a foot space can be restrained when the substrate area of a silicon wafer or the like is enlarged and cleaning performance is superior, and to provide a cleaning method.

SOLUTION: This semiconductor cleaning equipment is constituted of a treatment tank having a double structure formed of an internal tank 12 wherein an upper part is opened and a substrate is accommodated and an external tank 14 which so covers the internal tank that the internal tank can be tightly closed. At least one cleaning solution supply piping for supplying a cleaning solution from a cleaning solution inlet port 18 at the bottom of the internal tank and an internal tank drain pipe 20 for draining the solution of the internal tank are connected with the internal tank 12. Solvent containing gas supply piping 32 for supplying solvent containing gas for drying the substrate, solvent decomposing gas supply piping 34 for supplying solvent decomposing gas for decomposing a solvent component stuck on the substrate, an exhaust pipe 50 for discharging gas in the treatment tank and an external tank drain pipe 22 for draining a solution which overflows from the internal tank to the inside of the external tank are connected with the external tank 14.

